



#4 pre. amdt 9
#4 KDuncan
5.16.02

PATENT
ATTORNEY DOCKET NO.: 054216-5024

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Application of:)
)
Ki Seog KIM et al.)
) Group Art Unit: Unknown
Application No.: 10/029,390)
) Examiner: Unknown
Filed: December 28, 2001)
)
For: TEST PATTERN FOR MEASURING)
CONTACT RESISTANCE AND)
METHOD OF MANUFACTURING)
THE SAME)

Commissioner for Patents
Washington, D.C. 20231

Sir:

PRELIMINARY AMENDMENT

Prior to the examination of the above-identified application, please amend the
above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1-17, with the following:

- 91 1.(Amended) A test pattern for measuring a contact resistance, comprising:
a test wafer in which a plurality of device isolation ^{areas} ~~films~~ ^{object} are formed to
define a plurality of active regions;
a plurality of interconnection diffusion layers formed in a word line region ¹¹²
crossing the plurality of device isolation ^{areas} ~~films~~ ^{object} and the plurality of active regions;
^{parallel}
^{112?}